

a pedestal standing upright in the process chamber and connected to the worktable to support the worktable; and

a conduction structure configured to conduct static electricity generated on the worktable to a grounded portion outside the process chamber, the conduction structure having a conduction route for the static electricity including a conductive film formed on the worktable, formed on the pedestal, and electrically isolated from the casing of the chamber, wherein the conductive film is integrally formed and made of a same material as on the worktable and the pedestal.

35. (Amended) A single-substrate-processing apparatus, comprising:

an airtight process chamber including a casing and configured to process a target substrate;

a worktable configured to support the target substrate within the casing of the process chamber,

a pedestal connected to the worktable to support the worktable; and

a conduction structure configured to conduct static electricity generated on the worktable to a grounded portion outside the process chamber, the conduction structure having a conduction route for the static electricity including a conductive film formed on the worktable and the pedestal, the conduction structure being arranged such that the conductive film and a conductive portion of the casing are electrically connected to ground,

wherein the conductive film is integrally formed and made of a same material as on the worktable and the pedestal.